

**AMENDMENTS TO THE SPECIFICATION:**

Please replace the originally filed specification with a substitute specification as attached along with a marked-up copy of the originally filed specification.

**LISTING OF CLAIMS**

This listing of claims will replace all prior versions, and listings, of all claims as pending in the application, including newly added claims 21-22 and claims 1-4, 6, 11-14 and 20 as amended as follows:

**Claim 1 (Currently Amended):** ~~Method~~A method of measuring dimensions and alignment ~~error of a thin film magnetic head to monitor a lapping process~~heads formed on a substrate, including~~comprising~~ the steps of:

illuminating a magnetoresistance effect element and a resistance detector element which is formed for monitoring ~~the~~ a lapping process, both of which are formed on a the substrate, with illuminating light whose wavelength is 300 nm or less;

forming an image by imaging light reflected from said elements;  
converting said image to an image signal through photoelectric conversion;  
and

detecting dimensions and alignment error ~~geometrical information of the above-mentioned magnetoresistance effect element and the above-mentioned resistance detector element~~ formed on the substrate ~~for monitoring the lapping process~~ from said image signal.

**Claim 2 (Currently Amended):** ~~Method of measuring dimensions and alignment of a thin film magnetic head~~A method according to claim 1, wherein

the illuminating light includes a wavelength component of 248 nm.

**Claim 3 (Current Amended):** ~~Method of measuring dimensions and alignment of a thin film magnetic head~~A method according to claim 1, wherein the illuminating light includes a wavelength component of 266 nm.

**Claim 4 (Currently Amended):** ~~Method of measuring dimensions and alignment of a thin film magnetic head~~A method according to claim 1, wherein the illuminating light includes a wavelength component of 213 nm.

**Claim 5 (Cancel)**

**Claim 6 (Currently Amended):** ~~Method of measuring dimensions and alignment of a thin film magnetic head~~A method according to claim 1, wherein the magnetoresistance effect element and the resistance detector element for monitoring the lapping are covered with end face protection films.

**Claims 7-10 (Withdrawn)**

**Claim 11 (Currently Amended):** ~~Apparatus~~An apparatus for measuring dimensions and alignment ~~error~~ of thin film magnetic head~~heads~~ formed on a substrate during a lapping process, comprising:

- a light source for emitting light whose wavelength is 300 nm or less;
- illuminating means for illuminating a magnetoresistance effect element and a resistance detector element which is formed for monitoring the lapping process, both of which are formed on a substrate, with illuminating light emitted from said light source;

imaging means for obtaining an optical image of said substrate<sub>1</sub> illuminated by said illuminating means;

image pick up means for converting an optical image of said substrate<sub>1</sub> which is imaged by said imaging means, to an image signal through photoconversion; and

~~geometrical information-detecting means for detecting dimensions and alignment error geometrical information of said magnetoresistance effect element and said resistance detector element formed on the substrate for monitoring the lapping~~ from said image signal that is obtained by said image pick up means.

**Claim 12 (Currently Amended):**      ~~Apparatus for measuring dimensions and alignment of a thin film magnetic head~~An apparatus according to claim 11, wherein said light source emits light having a wavelength of 248 nm.

**Claim 13 (Currently Amended):**      ~~Apparatus for measuring dimensions and alignment of a thin film magnetic head~~An apparatus according to claim 11, wherein said light source emits light having a wavelength of 266 nm.

**Claim 14 (Currently Amended):**      ~~Apparatus for measuring dimensions and alignment of a thin film magnetic head~~An apparatus according to claim 11, wherein said light source emits light having a wavelength of 213 nm.

**Claims 15-16 (Cancel)**

**Claims 17-19 (Withdrawn)**

**Claim 20 (Currently Amended):**      ~~Method of measuring dimensions and alignment of a thin film magnetic head~~A method according to claim 1, wherein

the illuminating light has a wavelength of 200 nm.

**Claim 21 (Newly Added):** A method according to claim 1, further comprising a step of displaying the measured results at least one of the variations in dimensions of the elements or distribution of alignment error on a display.

**Claim 22 (Newly Added)** An apparatus according to claim 11, further comprising a display for displaying the measured results at least one of the variations in dimensions of the elements or distribution of alignment error.

**AMENDMENTS TO THE DRAWINGS:**

The attached sheets of drawings include changes to FIGs. 3, 4, 7, 9, 11-14 and 16. These sheets of drawings, which includes FIGs. 3, 4, 7, 9, 11-14 and 16, replaces the original sheets of drawings, including FIGs. 3, 4, 7, 9, 11-14 and 16.

**Attachment: Replacement Sheets.**